



UNITED STATES PATENT AND TRADEMARK OFFICE

UNITED STATES DEPARTMENT OF COMMERCE
United States Patent and Trademark Office
Address: COMMISSIONER FOR PATENTS
P.O. Box 1450
Alexandria, Virginia 22313-1450
www.uspto.gov

APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/709,055	04/09/2004	I-Chang Tsao	12404-US-PA	3054

31561 7590 08/09/2007

JIANQ CHYUN INTELLECTUAL PROPERTY OFFICE
7 FLOOR-1, NO. 100
ROOSEVELT ROAD, SECTION 2
TAIPEI, 100
TAIWAN

EXAMINER

ELVE, MARIA ALEXANDRA

ART UNIT	PAPER NUMBER
----------	--------------

1725

NOTIFICATION DATE	DELIVERY MODE
-------------------	---------------

08/09/2007

ELECTRONIC

Please find below and/or attached an Office communication concerning this application or proceeding.

The time period for reply, if any, is set in the attached communication.

Notice of the Office communication was sent electronically on above-indicated "Notification Date" to the following e-mail address(es):

USA@JCIPGROUP.COM.TW

Office Action Summary

Application No.

10/709,055

Applicant(s)

TSAO ET AL.

Examiner

M. Alexandra Elve

Art Unit

1725

-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --

Period for Reply

A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) OR THIRTY (30) DAYS, WHICHEVER IS LONGER, FROM THE MAILING DATE OF THIS COMMUNICATION.

- Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.
- If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.
- Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

Status

- 1) ☒ Responsive to communication(s) filed on 15 May 2007.
- 2a) ☐ This action is **FINAL**. 2b) ☒ This action is non-final.
- 3) ☐ Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11, 453 O.G. 213.

Disposition of Claims

- 4) ☒ Claim(s) 1-17 is/are pending in the application.
- 4a) Of the above claim(s) _____ is/are withdrawn from consideration.
- 5) ☐ Claim(s) _____ is/are allowed.
- 6) ☒ Claim(s) 1-17 is/are rejected.
- 7) ☐ Claim(s) _____ is/are objected to.
- 8) ☐ Claim(s) _____ are subject to restriction and/or election requirement.

Application Papers

- 9) ☐ The specification is objected to by the Examiner.
- 10) ☒ The drawing(s) filed on 09 April 2004 is/are: a) ☒ accepted or b) ☐ objected to by the Examiner.
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).
- 11) ☐ The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.

Priority under 35 U.S.C. § 119

- 12) ☒ Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
- a) ☒ All b) ☐ Some * c) ☐ None of:
1. ☒ Certified copies of the priority documents have been received.
2. ☐ Certified copies of the priority documents have been received in Application No. _____.
3. ☐ Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).

* See the attached detailed Office action for a list of the certified copies not received.

Attachment(s)

- 1) ☐ Notice of References Cited (PTO-892)
- 2) ☐ Notice of Draftsperson's Patent Drawing Review (PTO-948)
- 3) ☐ Information Disclosure Statement(s) (PTO/SB/08)
Paper No(s)/Mail Date _____
- 4) ☐ Interview Summary (PTO-413)
Paper No(s)/Mail Date _____
- 5) ☐ Notice of Informal Patent Application
- 6) ☐ Other: _____

DETAILED ACTION

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negated by the manner in which the invention was made.

Claims 1-5 & 12 are rejected under 35 U.S.C. 103(a) as being unpatentable over Yamazaki et al. (USPAP 2002/0004292) in view of Tanabe et al. (USPN 6,861,614).

Yamazaki et al. discloses a laser annealing apparatus and a method of annealing an amorphous silicon film. Laser light is generated and emitted from a source and then split. The split laser light is used to irradiate the front (primary beam) and the back (secondary beam) of the amorphous semiconductor film. This is shown in figures 3 and 18. It can be seen that the primary beam has a shorter path length than the secondary laser beam. An excimer laser may be used as the laser source. Additionally, an optical system may be used to generate harmonics. Photomasks may be used to generate predetermined patterns. The light source optical system is made up of a light source, an optical system, a reflector, a lens array, a polarization converting element and a condenser lens. (abstract, figures, 0005, 0049, 0061, 0063, 0104, 0128, 0129, 0180)

Although Yamazaki et al. discloses a photomask, the placing of the mask in the optical path is not taught.

Art Unit: 1725

Tanabe et al. discloses a system for forming and modifying thin silicon films. A photomask is used to project a light pattern, which exposes the thin film(s) and thus modifies them.

It would have been obvious to one of ordinary skill in the art at the time of the invention to use a photomask in the optical path, as taught by Tanabe et al. in the Yamazaki et al. system because allows more control of the film modification.

Duplication of parts was held to have been obvious. In re Harza 124 USPQ 378.

Claims 6-11 & 13-17 are rejected under 35 U.S.C. 103(a) as being unpatentable over Yamazaki et al. and Tanabe et al., as stated in the above paragraph and further in view of Jung (USPN 6,825,493).

Yamazaki et al. and Tanabe et al. do not teach (i) a photomask with a stripe pattern, (ii) a lens disposed on the optical path in front of the photomask and (iii) annealing amorphous silicon films in regions.

Jung discloses a silicon crystallization method using a photomask having a stripe pattern (38) and a condenser lens (40) is in front of the photomask. Figure 9b shows a striped crystallization pattern.

It would have been obvious to one of ordinary skill in the art at the time of the invention to use a striped photomask, a lens in front of the mask and annealing regions as taught by Jung in the Yamazaki et al. and Tanabe et al. apparatus and process because these are merely variations of silicon recrystallization using laser annealing.

Art Unit: 1725

Furthermore, it would have been obvious to use more than one photomask because it would enhance the efficiency of producing the product.

Response to Arguments

Applicant's arguments filed 5/15/07 have been fully considered but they are not persuasive.

Applicant argues that a second photomask is not taught by the prior art. The examiner respectfully notes that: Duplication of parts was held to have been obvious. In re Harza 124 USPQ 378.

Applicant argues that the position in the optical path is not disclosed. The examiner respectfully notes that: Although Yamazaki et al. discloses a photomask, the placing of the mask in the optical path is not taught.

Tanabe et al. discloses a system for forming and modifying thin silicon films. A photomask is used to project a light pattern, which exposes the thin film(s) and thus modifies them.

It would have been obvious to one of ordinary skill in the art at the time of the invention to use a photomask in the optical path, as taught by Tanabe et al. in the Yamazaki et al. system because allows more control of the film modification.

Art Unit: 1725

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to M. Alexandra Elve whose telephone number is 571-272-1173. The examiner can normally be reached on 7:30-4:00 Monday to Friday.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Jonathan Johnson can be reached on 571-272-1177. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

August 6, 2007.

/M. Alexandra Elve/
M. Alexandra Elve
Primary Examiner 1725